Abstract of Disclosure

METHOD FOR FORMING SEMICONDUCTOR LAYOUT PATTERNS, SEMICONDUCTOR LAYOUT PATTERNS, AND SEMICONDUCTOR STRUCTURE

A method for forming semiconductor layout patterns providing a pair of first layout patterns being symmetrical along an axial line, each of the first layout patterns comprising a first side proximal to the axial line and a second side far from the axial line; shifting a portion of the first layout patterns toward a direction opposite to the axial line to form at least a first shifted portion in each first layout pattern, and outputting the first layout patterns and the first shifted portions on a first mask.

Figure 1